

WEST Search History

DATE: Monday, March 31, 2003

Set Name Query
side by side

Hit Count Set Name
result set

DB=JPAB; PLUR=YES; OP=ADJ

L7	resist and (erod\$4 or erosion)	115	L7
L6	L5 and (etch\$3 NEAR6 plasma)	304	L6
L5	L4 and (semiconductor or silicon or Si)	4448	L5
L4	resist and (consum\$3 or selectiv\$3)	6166	L4

DB=EPAB; PLUR=YES; OP=ADJ

L3	resist and (erod\$4 or erosion)	20	L3
L2	L1 and (semiconduct\$3 or silicon or Si)	61	L2
L1	resist and (consum\$3 or selectiv\$3)	214	L1

END OF SEARCH HISTORY

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Set Name Query
side by side

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result set

DB=USPT; PLUR=YES; OP=ADJ

L6	L5 and plasma.clm.	313	L6
L5	L4 and (aspect ratio)	772	L5
L4	L3 and ((438/\$ or 216/\$ or 430/\$).ccls.)	4669	L4
L3	L2 and (etch\$3 NEAR6 plasma)	6778	L3
L2	L1 and (semiconduct\$3 or silicon or Si)	28318	L2
L1	resist and (consum\$3 or selectiv\$3 or erod\$3 or erosion)	68823	L1

END OF SEARCH HISTORY

energy; subclasses 487 + for polymerization of applied coating utilizing direct application of electrical, magnetic, wave, or particulate energy; subclasses 523 + for ion plating or ion implanting; subclasses 532 + for pretreatment of a substrate or posttreatment of a coated substrate utilizing electrical, magnetic, wave, or particulate energy; subclasses 569 + for deposition coating processes utilizing plasma; subclasses 580 + for deposition coating processes utilizing electrical discharge; subclass 581 for coating processes utilizing chemical liquid deposition; subclass 582 for coating processes utilizing photo-initiated chemical vapor deposition; subclasses 585 + for coating processes utilizing chemical vapor deposition; subclass 591 for deposition coating utilizing induction or dielectric heating; subclasses 592 + for deposition coating utilizing resistance heating; subclasses 595 + for deposition coating utilizing electromagnetic or particulate radiation; subclasses 598 + for deposition coating utilizing magnetic field or force; subclass 600 for deposition coating utilizing sonic or ultrasonic energy. (Coating operation not meeting Class 438 definition)

(1)

Note. Class 438 provides for a specie of Class 427 operations involving (a) coating a substrate with a semiconductive material or (b) coating a semiconductive substrate or substrate containing a semiconductive region; and wherein the intent is to use the electrical properties of the semiconductor in a solid state device for at least one of the following purposes: (i) conducting or modifying an electrical current, (ii) storing electrical energy for subsequent discharge within a microelectronic integrated circuit, or (iii) converting electromagnetic wave energy to electrical energy or electrical energy to electromagnetic energy.

(2)

Note. Generic claims with a sole claimed specie of coating for Class 438 goes as original to Class 438. Generic claims with a sole disclosed specie of coating for Class 438 goes as original in Class 438. Generic claims with plural claimed coating species wherein at least one of the claimed species does not belong in Class 438 goes as original in Class 427. Generic claims with plural disclosed coating species one of which does not belong in Class 438 goes to Class 427 as original. Generic claims with no material species claimed or disclosed goes as original in Class 427. When there is no generic claim and plural separately claimed coating specie, wherein at least one claim of which is Class 427 and one claim of which is Class 438, placement goes as original to Class 438 with a mandatory cross-reference to 427.

428, Stock Material or Miscellaneous Articles, appropriate subclasses for semiconductor stock material defined in terms of composition and structure, especially subclass 620. (see "Location of Semiconductor Compound, Composition, or Stock" above.)

429, Chemistry: Electrical Current Producing Apparatus, Product, and Process, especially subclass 7 for a combination including a nonbattery electrical component electrically connected within a cell casing other than testing or indicating components. (electrical class)

430, Radiation Imagery Chemistry: Process, Composition, or Product Thereof, particularly for initial lithographic processes in semiconductor manufacture limited to (a) exposure imaging and developing and including preparatory operations to the exposure (e.g., as coating to form the resist, etc.) or (b) developing, per se, of subject matter of Class 430 substrates. When Class

430 exposure, imaging or developing are combined with etching or coating of a semiconductor substrate for purposes other than masking and commensurate with the Class 438 definition for manufacture of a semiconductor device as set forth hereinabove, the combination goes as original to Class 438 with the following exception noted. (Coating operation not meeting Class 438 definition)

(1)

Note. Since Class 430 provides for processes of (a) coating, per se, of substrates, with a composition to produce a product to be used for electric or magnetic imagery and (b) processes of coating, per se, of substrate with a photosensitive composition for use in radiation imagery, coating or etching of semiconductor material limited to forming a product intended to be used for electric, magnetic, or radiation imagery is original in Class 430.

(2)

Note. Although technically classifiable as an original in Class 438 according to the above paragraph, any multistep process involving significant Class 430 operations as a subcombination of the overall process should be cross-referenced to Class 430.

430, Radiation Imagery Chemistry: Process, Composition, or Product Thereof, particularly for initial lithographic processes in semiconductor manufacture limited to (a) exposure imaging and developing and including preparatory operations to the exposure (e.g., as coating to form the resist, etc.) or (b) developing, per se, of subject matter of Class 430 substrates. When Class 430 exposure imaging or developing are combined with etching or coating of a semiconductor substrate commensurate with the Class 438 definition for manufacture of a semiconductor device as set forth hereinabove, the combination goes as original to Class 438 with the following exception noted. (Etching operation not meeting the Class 438 definition)

(1)

Note. Since Class 430 provides for processes of (a) coating, per se, of substrates, with a composition to produce a product to be used for electric or magnetic imagery and (b) processes of coating per se of substrate with a photosensitive composition for use in radiation imagery, coating or etching of semiconductor material limited to forming a product intended to be used for electric, magnetic, or radiation imagery is original in Class 430.

(2)

Note. Although technically classifiable as an original in Class 438 according to the above paragraph, any multistep process involving significant Class 430 operations as a subcombination of the overall process should be cross-referenced to Class 430.

repeat of above notes

432, Heating, for generic heating processes. However, inclusion of the criteria for Class 438 as set forth hereinabove takes the original to Class 438 even when generic heating is involved. (heating class)

439, Electrical Connectors, appropriate subclasses for features related or analogous to electrical contact or housing features of active solid-state devices (e.g., subclass 271 for sealing elements or subclasses 449 + for stress relief means for conductor to terminal joint. (electrical class)

501, Compositions: Ceramic, appropriate subclasses for ceramic compositions used in semiconductor devices. (see "Location of Semiconductor